L Number	Hits	Search Text	DB	Time stamp
1	1	("20030039893").PN.	US-PGPUB	2004/04/21 11:07
5	542	((phase adj shift$3 or phas$3 or shift$3) adj (mask or photomask) or PSM) same (resist or photoresist) and (second$3 or plural$3 or doubl$3 or mulipl$3 or repeat$3) near2 (expos$3 or radiat$3) and (resist or photoresist) same etch$3	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:22
7	7500	((phase adj shift$3 same (mask or photomask)) or phas$3 or shift$3) adj (mask or photomask) or PSM	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:34
8	2660	((phase adj shift$3 or (phas$3 or shift$3) adj (mask or photomask) or PSM)) same (resist or photoresist)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:37
9	561	((phase adj shift$3 or (phas$3 or shift$3) adj (mask or photomask) or PSM)) same (resist or photoresist) and (resist or photoresist) same (second$3 or plural$3 or doubl$3 or mulipl$3 or repeat$3) near2 (expos$3 or radiat$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:37
10	317	(((phase adj shift$3 or (phas$3 or shift$3) adj (mask or photomask) or PSM)) same (resist or photoresist) and (resist or photoresist) same (second$3 or plural$3 or doubl$3 or mulipl$3 or repeat$3) near2 (expos$3 or radiat$3)) and (phase adj shift$3 or (phas$3 or shift$3) near2 (mask or photomask) or PSM) same (period$3 or alternat$3 or repeat$3 or Levenson or Shibuya)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:39
12	303	((((phase adj shift$3 or (phas$3 or shift$3) adj (mask or photomask) or PSM)) same (resist or photoresist) and (resist or photoresist) same (second$3 or plural$3 or doubl$3 or mulipl$3 or repeat$3) near2 (expos$3 or radiat$3)) and (phase adj shift$3 or (phas$3 or shift$3) near2 (mask or photomask) or PSM) same (period$3 or alternat$3 or repeat$3 or Levenson or Shibuya)) and (phase adj shift$3 or (phas$3 or shift$3) near2 (mask or photomask) or PSM) same (align$4 or offset$4 or mov$3 or turn$3 or rotat$3 or position$3 or locat$3 or step$4)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:44
14	246	430/22,311-312,319,5,394.ccls. and (((((phase adj shift$3 or (phas$3 or shift$3) adj (mask or photomask) or PSM)) same (resist or photoresist) and (resist or photoresist) same (second$3 or plural$3 or doubl$3 or mulipl$3 or repeat$3) near2 (expos$3 or radiat$3)) and (phase adj shift$3 or (phas$3 or shift$3) near2 (mask or photomask) or PSM) same (period$3 or alternat$3 or repeat$3 or Levenson or Shibuya)) and (phase adj shift$3 or (phas$3 or shift$3) near2 (mask or photomask) or PSM) same (align$4 or offset$4 or mov$3 or turn$3 or rotat$3 or position$3 or locat$3 or step$4))	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/04/21 11:48